

### Abstract

A material for chemical vapor deposition of the present invention contains a precursor composed of a metal compound, and has 100 or less particles having a size of 0.5  $\mu\text{m}$  or more in 1 ml, in particle measurement by a light scattering type submerged particle detector in a liquid phase. A thin film can be prevented from being contaminated by particles even when a highly degradable metal compound is used as the precursor.